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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/813,687	03/31/2004	Patricius Aloysius Jacobus Tinnemans	081468-0308853	4349
	7590 08/31/200° VINTHROP SHAW PI	EXAMINER		
Eric S. Cherry	<ul> <li>Docketing Supervisor</li> </ul>	NGUYEN, HUNG		
P.O. BOX 10500 MCLEAN, VA 22102			ART UNIT	PAPER NUMBER
<b>,</b>		2851		
		•		
			MAIL DATE	DELIVERY MODE
			08/31/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

## Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)		
10/813,687	TINNEMANS ET AL.		
Examiner	Art Unit		
Hung Henry V. Nguyen	2851		

·	Hung Henry V. Nguyen	ו	2851	
The MAILING DATE of this communication app	ears on the cover sheet	with the co	orrespondence add	lress
THE REPLY FILED 23 August 2007 FAILS TO PLACE THIS A	PPLICATION IN CONDI	TION FOR A	ALLOWANCE.	
1.  The reply was filed after a final rejection, but prior to or o this application, applicant must timely file one of the folloplaces the application in condition for allowance; (2) a New a Request for Continued Examination (RCE) in compliant time periods:	n the same day as filing a wing replies: (1) an amer otice of Appeal (with appe	a Notice of Andment, affice all fee) in c	Appeal. To avoid aba davit, or other evider ompliance with 37 C	nce, which FR 41.31; or (3)
a) The period for reply expires <u>3</u> months from the mailing dat				
b) The period for reply expires on: (1) the mailing date of this no event, however, will the statutory period for reply expire Examiner Note: If box 1 is checked, check either box (a) or	later than SIX MONTHS from (b). ONLY CHECK BOX (b)	m the mailing	date of the final rejecti	on.
TWO MONTHS OF THE FINAL REJECTION. See MPEP		- 27 CED 4 41	26/a) and the engrapsis	uta autonojan faa
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of e under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office late may reduce any earned patent term adjustment. See 37 CFR 1.704(b)	ctension and the correspond shortened statutory period f ir than three months after the	ling amount of for reply origin	of the fee. The approprinally set in the final Offi	iate extension fee ice action; or (2) as
NOTICE OF APPEAL	nlianna with 27 CED 41 3	27 must be f	Flad within two montl	ha of the date of
<ol> <li>The Notice of Appeal was filed on A brief in comfiling the Notice of Appeal (37 CFR 41.37(a)), or any extension a Notice of Appeal has been filed, any reply must be filed.</li> </ol>	ension thereof (37 CFR 4	1.37(e)), to	avoid dismissal of th	ne appeal. Since
<u>AMENDMENTS</u>				
<ol> <li>The proposed amendment(s) filed after a final rejection.</li> <li>They raise new issues that would require further companies.</li> <li>They raise the issue of new matter (see NOTE bell)</li> </ol>	onsideration and/or searcow);	ch (see NOT	E below);	
(c) They are not deemed to place the application in be appeal; and/or		•		the issues for
(d) They present additional claims without canceling a	· -	or finally reje	ected claims.	
NOTE: (See 37 CFR 1.116 and 41.33(a)) 4. The amendments are not in compliance with 37 CFR 1.		of Non Co	mnliant Amendment	(PTOL-324)
5. Applicant's reply has overcome the following rejection(s		or Non-Cor	Inpliant Americanient	(I TOL-32-1).
Newly proposed or amended claim(s) would be a non-allowable claim(s).		a separate, t	timely filed amendme	ent canceling the
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is proof the status of the claim(s) is (or will be) as follows:			be entered and an e	explanation of
Claim(s) allowed: Claim(s) objected to:	· ·			
Claim(s) rejected: Claim(s) withdrawn from consideration:				
AFFIDAVIT OR OTHER EVIDENCE	•		•	
<ol> <li>The affidavit or other evidence filed after a final action, b because applicant failed to provide a showing of good awas not earlier presented. See 37 CFR 1.116(e).</li> </ol>	ut before or on the date on the date on the date of the sufficient reasons why	of filing a No the affidavi	otice of Appeal will <u>no</u> it or other evidence i	ot be entered s necessary and
9. The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to showing a good and sufficient reasons why it is necessar	overcome <u>all</u> rejections ι ry and was not earlier pre	under appea esented. Se	al and/or appellant fa se 37 CFR 41.33(d)(	ils to provide a 1).
10. $\square$ The affidavit or other evidence is entered. An explanati REQUEST FOR RECONSIDERATION/OTHER				
<ol> <li>The request for reconsideration has been considered been see attached sheet.</li> </ol>			condition for allowa	nce because:
12. $\boxtimes$ Note the attached Information Disclosure Statement(s)	(PTO/SB/08) Paper No(	s). <u>7/27/07</u>	10 .	
13.  Other:			Artenun	
			Hung Henry V Ngu	iyen .

Primary Examiner

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## Response to Arguments

Applicant's arguments filed 8/23/07 have been carefully reviewed but they are not 1. found persuasive. In response to Examiner's reasons for allowable subject matters, the Applicants can not point out the errors of the reasons for allowable subject matters stated in the Office Action sent December 15, 2006 as requested in the previous Office Action. However, applicants again state that "no one element or limitation in particular should be deemed to impart to or be required of the claims". Then, Applicants argue that "for example, claim 3 recites the aspects of the robot arm comprises a robot arm having a support frame for holding the object in addition to the aspects recited in independent claim 1" (see applicant's remarks, page 6, second paragraph); The Examiner respectfully disagrees with the applicants since this is not quite true. Firstly, the limitations on which the applicants rely are not stated in the claim. In fact, claim 3 calls for "the lithographic support system of claim 1wherein said compliant structure comprises two or more compliant rods that are rotatable at their ends". It is therefore shown that claim 3 specifically defines the structure of the compliant structure. Secondly, the Examiner would like to invite the applicant to re-visit section 7 of the mentioned office action. Therein it is stated that the prior art of record either alone or in combination, neither discloses nor makes obvious the combination of a lithographic support system comprising among other features, a compliant structure having specified structures for compensating at least a tilt and displacement between the object and the clamp, as recited in the mentioned claims of the present application. The Examiner restates that the above comments do accurately represent the actual claim language.

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Turning now to the prior art rejections, the applicant is reminded that the claimed subject matter to examination will be given their broadest reasonable interpretation consistent with the specification, and limitations appearing in the specification are not be read into the claims. In re Yamamoto, 740 F. 2d 1569, 1571, 222 USPO 934, 936 (Fed.Cir. 1984). With this in mind, the discussion herein will focus on how the terms and relationships thereof in the claims are met by the references. Response to any limitation that is not in the claims or any argument that is irrelevant to or does not relate to any specific claimed language will not be warranted.

Applicants argued that Hofer (U.S.Pat. 6,828,772) and Segers (U.S.Pat. 6,404,483) fail to teach "a lithographic support system comprising, inter alia, a compliant structure configured to compensate for at least one of a tilt and displacement between the object and the clamp, the compliant structure being provided at least between the rod and the support frame"; the Examiner disagrees. First, Hofer meets all of the limitations as claimed since Hofer discloses a lithographic support system (5) comprising: a moveable support structure (20, 60) to support and move a substrate (40) the support structure comprising a rod (20, 90) coupled a support frame that is provided with a clamp (60) for clamping the substrate (40) and a drive wheel edge assembly (50) can be regarded as a compliant structure for rotating the substrate to compensate for at least one of a tilt and displacement between the substrate (40) and the clamp (60). The compliant structure (50) is provided at least between the rod (20, 90) and the support frame (60) or on the support frame (60). As clearly illustrated from the disclosure of Hofer'772 (see figure 6A), the semiconductor wafer/object (40) is forced upward along an incline area on the wedge assemblies (50 and 55), thus one of the functions of the

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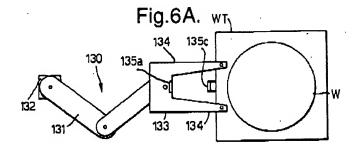
wedge assemblies (50 and 55) is to secure the wafer and to neutralize the effect of variations (such as the displacement) between the wafer/object and the clamp (60) (see col.6, lines 2-24). Hofer furthermore teaches that the support structure (5) has a robot arm (see figure 6) with a support frame (60) for holding the substrate (40) and the compliant structure (50) is provided between the rod (20, 90) and support frame (60) and the clamp is in contact with the object. (see figure 6). In figures 3a and 3b of the present application, the compliant is positioned between the rod (12), the intermediate part (16) and the support frame (18). Similarity, the compliant structure (50) in the reference of Hofer can be considered to be positioned between the rod (20) and the frame (60).

Second, Segers meets all of the limitations as recited. As discussed, Segers et al discloses a lithographic apparatus and corresponding method (see figure 1) comprising all structures set forth in the instant claims including: a radiation system (LA) configured to provide a beam of radiation; a support structure (MT) for supporting a patterning device (M); a substrate holder (WT) for holding a substrate (W); a projection optical system (PL) for projecting the patterned formed on the patterning device onto the substrate; and a support system for holding and moving one of the substrate, the patterning device; the support structure (see figure 5A) having a robot arm (130) having a rod (131) coupled to a support frame that is provided with a clamp (134) for clamping the substrate (W) and Segers teaches a compliant structure (135a) for compensating at least one of a tilt and displacement between the substrate (W) and the clamp (134) (see col.7, lines 10-25) wherein the compliance structure can be considered as being provided on the rod or the support frame (see figure 5c) so as to be contactless relationship with the object or being provided between the rod (131) and the support frame. In the reference of Segers, the

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compliant (135a) can be considered to be located between the rod (131) and the frame (133,134).



For the above reasons, the 102 (e) rejection of claims 1, 5-10, 15, 26-27 under the art of Hofer and the 102(b) rejection of claims 1, 5-6, 8, 10, 15, 18, 21, 23-27 under the art of Seger are maintained.

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hung Henry V. Nguyen whose telephone number is 571-272-2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Diane Lee can be reached on 571-272-2399. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Hung Henry V Nguyen Primary Examiner Art Unit 2851

hvn 8/28/07